

<b>Notice of References Cited</b>	Application/Control No. 10/753,673		Applicant(s)/Patent Under Reexamination LIU ET AL.	
	Examiner Johannes P. Mondt		Art Unit 3663	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,914,514	06-1999	Dejenfelt et al.	257/322
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	T	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	S. Wolf, "Silicon Processing for the VLSI Era", Volume 2 - Process Integration, (Lattice Press, Sunset Beach, m California, (1990), Chapter 9, pp. 658-663, especially figure 9-10.
	V	R. B. Fair, "Diffusion and Ion Implantation in Silicon", Chapter 7 in "Semiconductor Materials and Process Technology Handbook", William Andrew Publishing / Noyes, Ed.: G.E. McGuire (1988), espially the discussion on crtical energy (page 520).
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.